

IFW



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No. : 10/723,714 : Confirmation No.: 9797
Applicant : Bing Ji et al.
Filed : November 26, 2003
For : METHOD FOR ETCHING HIGH DIELECTRIC CONSTANT
MATERIALS AND FOR CLEANING DEPOSITION CHAMBERS FOR
HIGH DIELECTRIC MATERIALS

Art Unit : 1763
Examiner : George A. Goudreau

Docket No. : 06299P2USA
Customer No. : 23543

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING	
I CERTIFY THAT THIS PAPER (ALONG WITH ANY PAPER REFERRED TO AS BEING ATTACHED OR ENCLOSED) IS BEING DEPOSITED WITH THE UNITED STATES POSTAL SERVICE WITH SUFFICIENT POSTAGE AS FIRST CLASS MAIL IN AN ENVELOPE ADDRESSED TO:	
COMMISSIONER FOR PATENTS P.O. BOX 1450 ALEXANDRIA, VA 22313-1450	
ON	<u>Feb. 17, 2005</u>
	Date
<u>Rosaleen P. Morris-Oskanian</u>	
(Type or print name of person mailing paper)	
<u><i>Rosaleen P. Morris-Oskanian</i></u>	
Signature of person mailing paper	

Response to Restriction Requirement

Sir:

The following is responsive to the Office Action dated January 18, 2005:

- ☐ **Amendments to the Specification** begin on page _____ of this paper.
- ☒ **Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.
- ☐ **Amendments to the Drawings** begin on page _____ of this paper and include an attached replacement sheet(s).
- ☐ **Amendments to the Abstract** are on page _____ of this paper. A clean version of the Abstract is on page _____ of this paper.
- ☒ **Remarks/Arguments** begin on page 7 of this paper.